



PATENT
81839.0107

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Makoto IIDA, et al.

Serial No: 10/009,910

Filed: December 12, 2001

For: SILICON WAFER, SILICON EPITAXIAL
WAFER, ANNEAL WAFER AND METHOD
FOR PRODUCING THEM

Art Unit: 1765

Examiner: Matthew J. Song

PETITION FOR EXTENSION OF TIME

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

I hereby certify that this correspondence
is being deposited with the United States
Postal Service with sufficient postage as
first class mail in an envelope addressed
to:

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450, on
November 2, 2004

Date of Deposit

John P. Scherlacher, Reg. No. 23,009

Name

Signature

Date

Dear Sir:

In accordance with 37 C.F.R. 1.136, Applicant respectfully petitions the
Commissioner for a two-month extension of time extending to November 24, 2004,
the period for response to the final Office Action dated June 24, 2004. Please charge
the fee of \$430 for this extension to Deposit Account No. 50-1314. The responsive
paper(s) are attached.

Please charge any insufficiency or credit any overpayment to Deposit Account
No. 50-1314. A copy of this petition is enclosed.

Respectfully submitted,

HOGAN & HARTSON L.L.P.

Date: November 2, 2004

By:

John P. Scherlacher
Registration No. 23,009
Attorney for Applicant(s)

500 South Grand Avenue, Suite 1900
Los Angeles, California 90071
Phone: 213-337-6700
Fax: 213-337-6701

10009910

11/08/2004 RHEBRIGHT 00000003 501314

430.00 DA

01 FC:1252